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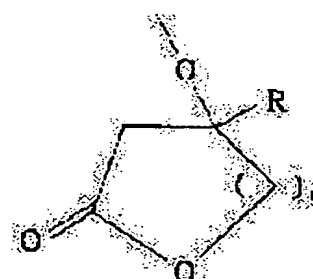
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(54) RESIST COMPOSITION AND RESIST PATTERN FORMING METHOD

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain a resist compsn. having a sensitivity capable of practical use and capable of forming a nonswellable fine resist pattern.

SOLUTION: An acid-sensitive polymer contained in this chemical amplification type resist compsn. in combination with an optical acid generating agent contains a lactone part represented by the formula [where R is optionally subst. 1-4C straight chain or branched chain alkyl and (n) is an integer of 1-4] as a protective group for each carboxyl group.



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